

SU-8 2100 – run sheet

MicroChem

nanyte.com/photoresists/su-8-2100 · last updated 2026-07-26

Thickness: 103–269 μm

Exposure dose – dose by film thickness

Film thickness	Dose
100–150 μm	240–260 mJ/cm^2
160–225 μm	260–350 mJ/cm^2
230–270 μm	350–370 mJ/cm^2
280–550 μm	370–600 mJ/cm^2

Develop: Developer SU-8 Developer (MicroChem) · Rinse IPA ·
Method immersion

Hardbake: 150–250 $^{\circ}\text{C}$ · 5–30 min